

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Hayashi et al.
Appl. No.	:	10/565,696
Filed	:	January 24, 2006
For:	:	RESIN FOR RESIST, POSITIVE RESIST COMPOSITION, AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Huhn, R.
Group Art Unit	:	4131

AMENDMENT AND RESPONSE TO OFFICE ACTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **June 30, 2009**, please amend the above-referenced application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Summary of Examiner Interview begins on page 6 of this paper.

Remarks/Arguments begin on page 7 of this paper.